

WHAT IS CLAIMED IS:

1. A reflective light processing element, comprising:
a substrate;
a dielectric layer formed on the substrate;
5 a conductive trace formed on the dielectric layer, the conductive trace allowing charges trapped in the dielectric layer to escape; and
a plurality of ribbons formed above the substrate and the conductive trace.
2. A high contrast grating light valve comprising a silicon substrate;
a protective dielectric layer formed on the substrate;
10 a first set of ribbons each with a first average width W_a and a second set of ribbons each with a second average width W_b , wherein the ribbons of the first set alternate between the ribbons of the second set and, one of said first and second set of ribbons is configured to move relative to the other to constructively and destructively interfere with an incident light source having a wavelength X ;
15 wherein said substrate comprises a silicon wafer protected by a dielectric layer;
and
a conductive trace formed at least partly on the protective layer and in electrical contact with said substrate, allowing charges trapped in the protective layer to escape.
- 20 3. The grating light valve of Claim 2, wherein said dielectric layer comprises silicon dioxide.

